

<b>Notice of References Cited</b>	Application/Control No. 09/249,728	Applicant(s)/Patent Under Reexamination LOPEZ ET AL.	
	Examiner Mehrdad Dastouri	Art Unit 2623	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Budd et al, "Development and Application of a New Tool for Lithographic Mask Evaluation, the Stepper Equivalent Aerial Image Measurement System (AIMS)", 1997, IBM Journal of Research and Development, Vol. 41, No. 1/2
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